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(Use several sheets if necessary)

Applicant Name

10/789,083

Bang-Ching Ho et al.

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Group 21 Univ

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[illegible]

## FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Portion or Pages, Etc.)

Dr-	Ding et al. "Optimization of Bottom Antireflective Coating Materials for Dual Damascene Process", <u>SPIE Proceedings</u> , 3999, (2000), pp. 910 - 918.
Th-	Pollentier et al., "Dual Damascene Back-End Patterning Using 248 nm and 193 nm Lithography", <u>Interface 2000</u> , pp. 265-283.

ΟΛΥΜΠΙΑ

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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

